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ABSTRACT OF THE DISCLOSURE

A scan type exposure apparatus in which a pattern formed on an original is transferred a substrate while relatively moving the original and the substrate relative to a projection optical system, wherein a stage is servo controlled on the basis of measurement ϕf X and Y coordinates (x,y) and yawing component 0, and wherein yawing measuring systems provided in relation to X and Y directions are selectively used in accordance with the state of operation of the apparatus so that the yawing component measurement direction is laid on preferable one of the X and Y directions.

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